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(54) Title: MAINTENANCE METHODS FOR POLISHING SYSTEMS AND ARTICLES RELATED THERETO

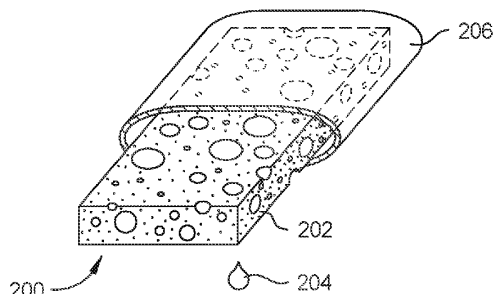


FIG. 2

(57) Abstract: Embodiments herein relate to chemically impregnated applicators, which may be used to provide hydrophobic surfaces on CMP system components and related application methods. In one embodiment, a method of forming a hydrophobic coating on a surface of a polishing system component includes cleaning the surface of the polishing system component to remove a polishing fluid residue therefrom and applying a hydrophobicity causing chemical solution to the surface of the polishing system component.

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